

APR 27 2005

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. .... 10/806,923  
Filing Date ..... March 22, 2004  
Inventor ..... Weimin Li et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2812  
Examiner ..... Unknown  
Attorney Docket No. .... MI22-2274  
Customer No. .... 021567  
Title: Methods of Depositing Silicon Dioxide Comprising Layers in the  
Fabrication of Integrated Circuitry, Methods of Forming Trench Isolation,  
and Methods of Forming Arrays of Memory Cells

Assistant Commissioner for Patents  
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2. Transmittal Form (PTO/SB/21)
3. Cited References (5)

Dated: 4/27/05By: 

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NUMBER OF PAGES IN FACSIMILE: 27

PTO/SB/21 (03-03)

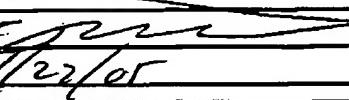
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<b>TRANSMITTAL FORM</b> <i>(to be used for all correspondence after initial filing)</i>		Application Number 10/808,923
Total Number of Pages in This Submission		Filing Date March 22, 2004
		First Named Inventor Welmin Li et al.
		Art Unit 2812
		Examiner Name Unknown
		Attorney Docket Number MI22-2274

ENCLOSURES (Check all that apply)		
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Firm or Individual	Mark S. Matkin, Reg. No. 32,268 Wells St. John, P.S.
Signature	
Date	4/22/05

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**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to 1276 OG 55, August 5, 2003, no copies of cited U.S. patents or U.S. patent application publications are included, as the date of filing of this patent application occurs after June 30, 2003. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 4-27-05By:   
Mark S. Matkin  
Reg. No. 32,268

Sheet 1 of 2

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTORNEY DOCKET NO. MI22-2274	SERIAL NO. 10/806,923
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Weimin Li et al.	
		FILING DATE March 22, 2004	GROUP ART UNIT 2812

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,013,583	1/11/2000	Ajmera et al.			
	AB	2001/0041250 A1	11/2001	Haukka et al.			
	AC	2002/0000195 A1	1/2002	Kao et al.			
	AD	2002/0018849	2/2002	George et al.			
	AE	2003/0032281 A1	2/13/2003	Werkhoven et al.			
	AF	2003/00129826 A1	7/10/2003	Werkhoven et al.			
	AG	2004/0209484	10/2004	Hill et al.			
	AH	2004/0266153 A1	12/30/2004	Yongjun Jeff Hu			

FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes
	AI	EP 0817251 A	1/1998	EPO			
	AJ						No

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER	AK	PCT/US2004/021156; Filed 6/30/2004; Search Report.					
EXAMINER		DATE CONSIDERED					

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2274	SERIAL NO. 10/806,923
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Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						

FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes
	AF						
	AG						
	AH						

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	A	Chen et al., <i>Excimer Laser-Induced Ti Silicidation to Eliminate the Fine-Line Effect for Integrated Circuitry Device Fabrication</i> , 149 JOURNAL OF ELECTROCHEMICAL SOCIETY, No. 11, pp. G609-G612 (2002).	
	AJ	Nishiyama et al., <i>Agglomeration Resistant Self-Aligned Silicide Process Using N<sub>2</sub> Implantation into TiSi<sub>2</sub></i> , 36 JPN. J. APPL. PHYS., Part 1, No. 6A, pp. 3639-3643 (June 1997).	
	AK	Wolff, Chapter 13: <i>Polycides and Salicides of TiSi<sub>x</sub>, CoSi<sub>2</sub>, and NiSi</i> , SILICON PROCESSING FOR THE VLSI ERA, Vol. IV, pp. 603-604 (pre-2003).	
EXAMINER		DATE CONSIDERED	
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